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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/995,031	11/29/2001	Ricky Amos	YOR920010633US1 (062) 9669	
7590 10/12/2004			EXAMINER	
TUNG & ASSOCIATES			LANDAU, MATTHEW C	
Suite 120				
838 W. Long Lake Road			ART UNIT	PAPER NUMBER
Bloomfield Hills, MI 48302			2815	

DATE MAILED: 10/12/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
Office Action Summer	09/995,031	AMOS ET AL.			
Office Action Summary	Examiner	Art Unit			
	Matthew Landau	2815			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	correspondence address			
A SHORTENED STATUTORY PERIOD FOR REPL' THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period of the provided of the	36(a). In no event, however, may a reply be tin y within the statutory minimum of thirty (30) day vill apply and will expire SIX (6) MONTHS from , cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 24 M	arch 2003.				
2a) ☐ This action is FINAL . 2b) ☑ This	action is non-final.	· •			
3) Since this application is in condition for allowar	nce except for formal matters, pro	secution as to the merits is			
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.			
Disposition of Claims					
4) Claim(s) <u>1-23</u> is/are pending in the application.					
4a) Of the above claim(s) <u>17-23</u> is/are withdraw					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-16</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/o	r election requirement.				
Application Papers					
9) The specification is objected to by the Examine	г.				
10) The drawing(s) filed on is/are: a) acc	epted or b) objected to by the I	Examiner.			
Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).			
Replacement drawing sheet(s) including the correct	ion is required if the drawing(s) is ob	jected to. See 37 CFR 1.121(d).			
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) ☐ Acknowledgment is made of a claim for foreign a) ☐ All b) ☐ Some * c) ☐ None of:	priority under 35 U.S.C. § 119(a))-(d) or (f).			
·-	1. Certified copies of the priority documents have been received.				
2. Certified copies of the priority documents		on No			
3. Copies of the certified copies of the prior	ity documents have been receive	ed in this National Stage			
application from the International Bureau	ı (PCT Rule 17.2(a)).				
* See the attached detailed Office action for a list	of the certified copies not receive	ed.			
Attachment(s)) Notice of References Cited (PTO-892)	a) 🔲 lmbar: :: 0	(DTO 442)			
?) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4)	ite			
) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	5) Notice of Informal P 6) Other:	atent Application (P.TO-152)			
Tupor Ho(s)/High Date	o) Outer,				

DETAILED ACTION

Claim Objections

Claim 6 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim. Applicant is required to cancel the claim(s), or amend the claim(s) to place the claim(s) in proper dependent form, or rewrite the claim(s) in independent form. Claim 1 recites "a semi-conducting substrate having source and drain regions". Therefore, the limitation "wherein said semi-conducting substrate has at least one source and one drain region" (claim 6) does not further limit claim 1, from which it depends. A substrate that has "source and drain regions" inherently has "at least one source region and one drain region".

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-3, 5-12, and 14-16 are rejected under 35 U.S.C. 102(e) as being anticipated by Dokumaci et al. (US Pat. 6,514,843, hereinafter Dokumaci).

Regarding claims 1-3, 5-12, and 14-16, Figure 1F of Dokumaci discloses a metal oxide semiconductor field effect (MOSFET) device comprising: a semiconducting substrate 10 (Si, n or p-type)(col. 3, lines 14-16) having source/drain regions 26; a gate dielectric layer 12 (SiO₂) of

0.5 nm thickness (col. 3, lines 45-47) on the substrate; and a gate 16 formed of Rh (col. 3, lines

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53-55) on top of said gate dielectric layer.

Claims 1-16 are rejected under 35 U.S.C. 102(e) as being anticipated by Lee et al. (US

Pat. 6,614,079, hereinafter Lee).

In regards to claims 1-16, Figure 1 of Lee discloses a metal oxide semiconductor field

effect (MOSFET) device comprising: a semiconducting substrate 10 (Si, n or p-type)(col. 5, lines

15-22) having source/drain regions 15; a gate dielectric layer 14 (SiO₂ or HfO₂) (col. 5, lines 55-

58) of 1.5 nm thickness (col. 5, lines 48-50) on the substrate; and a gate 16 formed of Rh (col. 6,

lines 1-3) on top of said gate dielectric layer.

Response to Arguments

Applicant's arguments with respect to claims 1-16 have been considered but are moot in

view of the new ground(s) of rejection.

Conclusion

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Matthew C. Landau whose telephone number is (571) 272-1731.

The examiner can normally be reached from 8:30 AM - 5:30 PM. If attempts to reach the

examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached

on (571) 272-1664. The fax phone numbers for the organization where this application or

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proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9306 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

TON THOMAS

SUPERVISORY PUTENT EXAMINER TECHNOLOGY CENTER 2800

Matthew C. Landau

Examiner

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September 29, 2004